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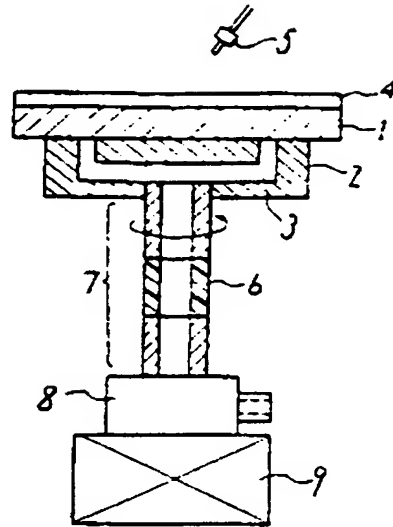
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ABSTRACT : PURPOSE: To inhibit the temperature rise of a wafer and to contrive the improvement of reproducibility of the film thickness of the resist film between the wafers by a method wherein a heat-insulating material is used for parts of the supporting rods of a vacuum chuck for fixing the wafer.

CONSTITUTION: When a wafer 1 is fixed on a vacuum chuck 2, a resist liquid is dripped through a nozzle 5, a motor 9 begins to rotate and the wafer 1 is rotated along with the vacuum chuck 2. The resist liquid applies a uniform resist film on the wafer 1 by a centrifugal force generated by this rotation. At this time, heat generated from the motor 9 does not transmit to the wafer 1 because heat-insulating materials 6 are held between the motor 9 and the vacuum chuck 2. Thereby, as the temperature rise of the wafer is not generated, the viscosity of the resist liquid dripped on the wafer 1 becomes constant between the wafers and the film thickness of the resist film can be controlled with good reproducibility.

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